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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/709,055	04/09/2004	I-Chang Tsao	12404-US-PA	3054	
31561	7590 09/07/2005		EXAM	INER	
JIANQ CHYUN INTELLECTUAL PROPERTY OFFICE 7 FLOOR-1, NO. 100			ELVE, MARIA	ELVE, MARIA ALEXANDRA	
ROOSEVELT ROAD, SECTION 2			ART UNIT	PAPER NUMBER	
TAIPEI, 100			1725		
TAIWAN	TAIWAN		DATE MAILED: 09/07/2005		

Please find below and/or attached an Office communication concerning this application or proceeding.

	Application No.	Applicant(s)				
Office Action Summers	10/709,055	TSAO ET AL.				
Office Action Summary	Examiner	Art Unit				
	M. Alexandra Elve	1725				
The MAILING DATE of this communication app Period for Reply	pears on the cover sheet with the	correspondence address				
A SHORTENED STATUTORY PERIOD FOR REPL WHICHEVER IS LONGER, FROM THE MAILING D  - Extensions of time may be available under the provisions of 37 CFR 1.1 after SIX (6) MONTHS from the mailing date of this communication.  - If NO period for reply is specified above, the maximum statutory period  - Failure to reply within the set or extended period for reply will, by statute Any reply received by the Office later than three months after the mailine earned patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION  ATE OF THIS COMMUNICATION  BY A THIS COMMUNICATION  WILLIAM AND A THIS COMMUNICATION  COMMUNICATION	DN, limely filed  m the mailing date of this communication.  IED (35.U.S.C. & 133)				
Status	•					
1) Responsive to communication(s) filed on						
	—· s action is non-final.					
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closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.						
Disposition of Claims						
4)⊠ Claim(s) <u>1-17</u> is/are pending in the application						
4a) Of the above claim(s) is/are withdrawn from consideration.						
5) Claim(s) is/are allowed.						
6)⊠ Claim(s) 1-17 is/are rejected.						
7) Claim(s) is/are objected to.	7) Claim(s) is/are objected to.					
8) Claim(s) are subject to restriction and/o	r election requirement.	·				
Application Papers						
9) The specification is objected to by the Examiner.						
10)☑ The drawing(s) filed on <u>09 April 2004</u> is/are: a)☑ accepted or b)☐ objected to by the Examiner.						
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).						
Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).						
11) The oath or declaration is objected to by the Examiner. Note the attached Office Action or form PTO-152.						
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).  a) ☑ All b) ☐ Some * c) ☐ None of:  1. ☑ Certified copies of the priority documents have been received.  2. ☐ Certified copies of the priority documents have been received in Application No						
Copies of the certified copies of the prior application from the International Bureau     See the attached detailed Office action for a list	ı (PCT Rule 17.2(a)).					
•••						
Attachment(s)  1) Notice of References Cited (PTO-892)  4) Interview Summary (PTO-413)						
2) Notice of Draftsperson's Patent Drawing Review (PTO-948) Paper No(s)/Mail Date.						
B) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date	5) 🔲 Notice of Informal I	Patent Application (PTO-152)				
Patent and Trademark Office	6)					

#### **DETAILED ACTION**

### Claim Objections

Claim 1 is objected to because of the following informalities: "saidamorphous".

Appropriate correction is required.

## Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1-5 & 12 are rejected under 35 U.S.C. 102(b) as being anticipated by Yamazaki et al. (USPAP 2002/0004292).

Yamazaki et al. discloses a laser annealing apparatus and a method of annealing an amorphous silicon film. Laser light is generated and emitted from a source and then split. The split laser light is used to irradiate the front (primary beam) and the back (secondary beam) of the amorphous semiconductor film. This is shown in figures 3 and 18. It can be seen that the primary beam has a shorter path length than the secondary laser beam. An excimer laser may be used as the laser source. Additionally, an optical system may be used to generate harmonics. Photomasks may be used to generate predetermined patterns. The light source optical system is made up of a light source, an optical system, a reflector, a lens array, a polarization converting element and a condenser lens. (abstract, figures, 0005, 0049, 0061, 0063, 0104, 0128, 0129, 0180)

## Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 6-11 & 13-17 are rejected under 35 U.S.C. 103(a) as being unpatentable over Yamazaki et al., as stated in the above paragraph and further in view of Jung (USPN 6,825,493).

Yamazaki et al. does not teach (i) a photomask with a stripe pattern, (ii) a lens disposed on the optical path in front of the photomask and (iii) annealing amorphous silicon films in regions.

Jung discloses a silicon crystallization method which uses a photomask having a stripe pattern (38) and a condenser lens (40) is in front of the photomask. Figure 9b shows a striped crystallization pattern.

It would have been obvious to one of ordinary skill in the art at the time of the invention to use a striped photomask, a lens in front of the mask and annealing regions as taught by Jung in the Yamazaki et al. apparatus and process because these are merely variations of silicon recrystallization using laser annealing.

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#### Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. See US PTO-892.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to M. Alexandra Elve whose telephone number is 571-272-1173. The examiner can normally be reached on 6:30-3:00 Monday to Friday.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Tom Dunn can be reached on 571-272-1171. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

September 4, 2005.

M. Alexandra Elve Primary Examiner 1725